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Nanotechnology and Microelectronics: Materials, Processing, Measurement, and Phenomena

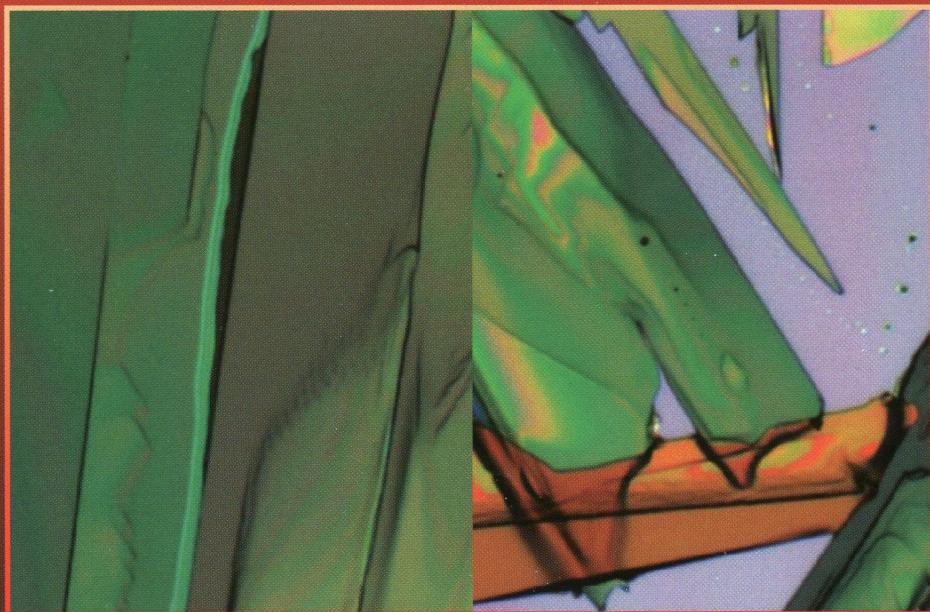


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Journal of Vacuum Science & Technology B

JVST B

Nanotechnology and Microelectronics: Materials, Processing, Measurement, and Phenomena

Second Series
Volume 32, Number 5
Sep/Oct 2014

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[J. Vac. Sci. Technol., B 32, 040801 (2014)]

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On The Cover: Kyeiwa Asare-Yeboah, Rachel M. Frazier, Greg Szulczewski, and Dawen Li, JVST B 32(5), p. 052401-1 (2014). Cover shows the enhancement of TIPS pentacene crystalline film resulting from the temperature-gradient technique.